

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Applicants: Ogata et al.

Examiner: Lee, Sin J

Application No.: 10/589,382

Group Art Unit: 1795

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Docket: 1608-6 PCT/US

For: **PHOTORESIST COMPOSITION AND METHOD OF FORMING RESIST PATTERN** Dated: July 3, 2008

Confirmation No.: 6030

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Dated: July 3, 2008

Signature: Barbara Thomas

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

**RESPONSE TO OFFICE ACTION UNDER 37 C.F.R. §1.111**

Sir:

In response to the non-final Office Action dated April 3, 2008, the due date for which is July 3, 2008, please amend the above-identified application as follows:

**Amendments to the Claims** are reflected in the listing of claims which begins on page 2 of this paper.

**Remarks** begin on page 5 of this paper.